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Commissioner of Patents and Trademarks Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572 20 McIntosh Drive Poughkeepsie, N.Y. 12603

Subject:

Serial No. 09/769 812 01/26/01

Li-Te Lin, Li-Chih Chao, Chia-Shiung Tsai

AN ORGANIC LOW K DIELECTRIC ETCH WITH NH3 CHEMISTRY

| Grp. Art Unit: 1<del>743</del> | 1746

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INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 6,071,815 to Kleinhenz et al., "Method of Patterning Sidewalls of a Trench in Integrated Circuit Manufacturing", discloses a silicon oxide layer etch that uses HF and ammonia in combination with other gases.

Commissioner of Patents and Trademarks

Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572

20 McIntosh Drive

Poughkeepsie, N.Y. 12603

Subject:

Serial No. 09/769,812 01/26/01

Li-Te Lin, Li-Chih Chao, Chia-Shiung Tsai

AN ORGANIC LOW K DIELECTRIC ETCH WITH NH3 CHEMISTRY

Grp. Art Unit: 1743

## ASSOCIATE POWER OF ATTORNEY

I hereby appoint William Stoffel, registration number 39,390, as my associate attorney in this case. His telephone number is (215) 564-2258.

Please continue to direct all correspondence in this case to the undersigned attorney.

Respectfully submitted,

Stephen B. Ackerman,

Principal attorney of record

## 1 TSMC-00-240

- U.S. Patent 5,897,377 to Suzuki, "Semiconductor Device Manufacturing Method with Use of Gas Including Acyl-Group-Containing Compound", discloses a surface treatment etch.
- U.S. Patent 5,972,235 to Brigham et al., "Plasma Etching Using Polycarbonate Mask and Low Pressure-High Density Plasma", discloses a low-k etch.
- U.S. Patent 6,063,712 to Gilton et al., "Oxide Etch and Method of Etching", teaches an oxide etch using ammonia a fluorine containing compound and a boron containing compound.

Sincerely

Stephen B. Ackerman, Reg. No. 37761